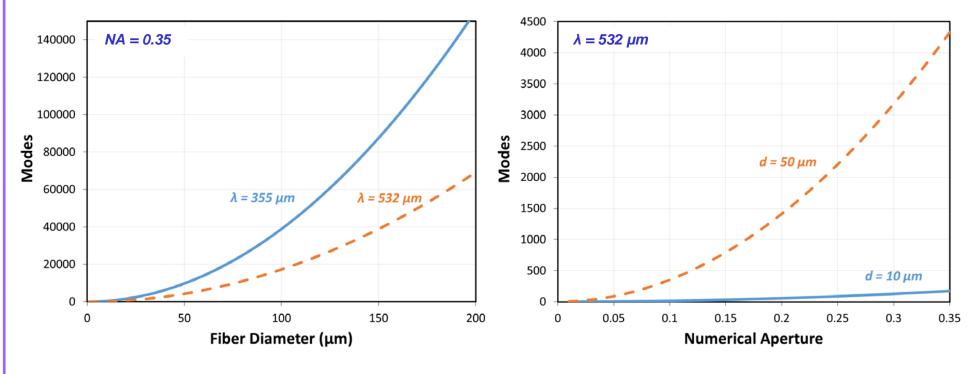
Reduced Mode Sapphire Optical Fiber and Sensing System

4

Motivation

Monitoring systems have been shown to improve the reliability, efficiency, safety and security of advanced combustion and gasification. The ability to tailor the structure of single crystal sapphire fibers has the potential to enhance the performance of high temperature fiber optic sensors. The proposed sapphire fiber waveguide design will overcome the harsh environment challenges that severely limit the integration of mature optical fiber sensing technologies in new power plant control systems.

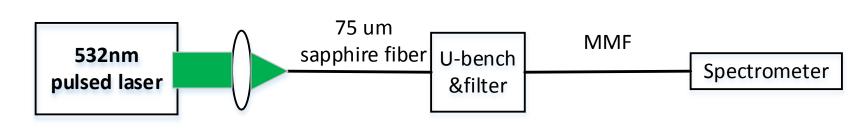
Low Modal Volume Sapphire Fiber

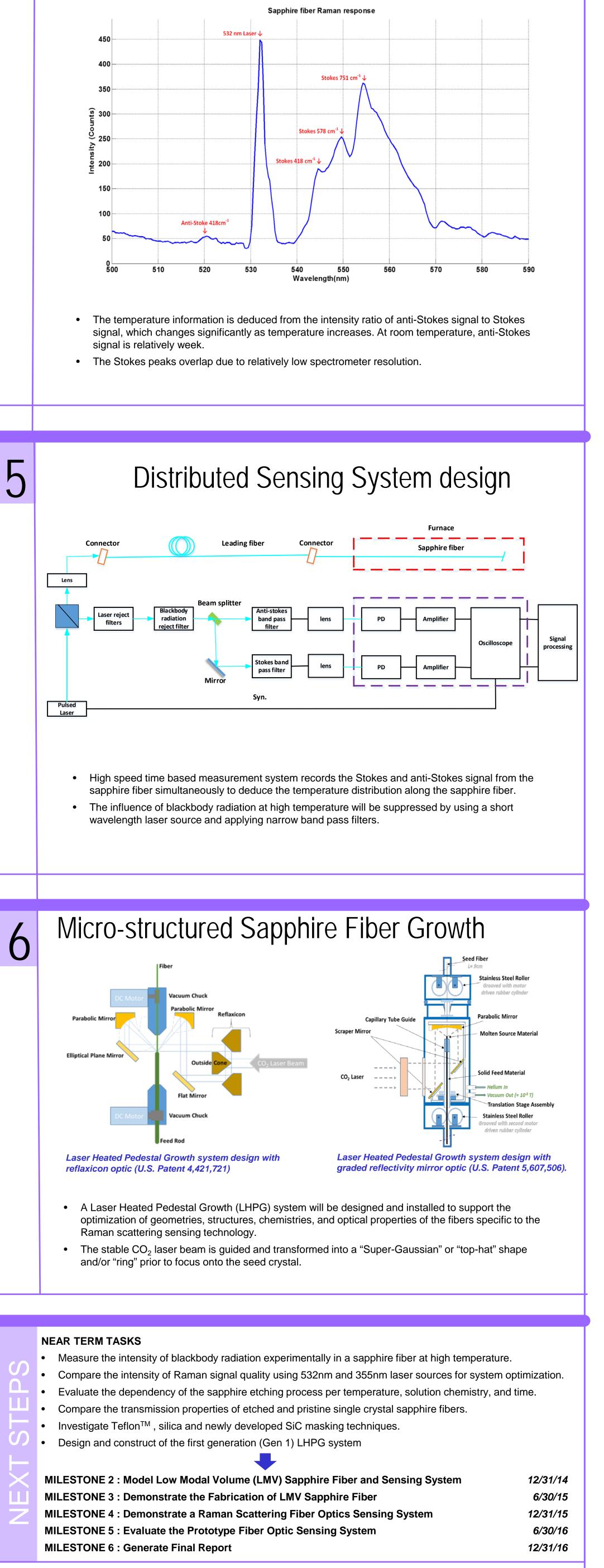


The number of modes as a function of the sapphire fiber diameter (left) and Numerical Apertures (right).

- The large modal volume of sapphire fibers limits the performance of Raman scattering FO sensing systems.
- The number of modes, M, in fibers with large V parameters can be estimated by $M = (4/\pi^2) V^2$.
- The number of modes can be modified by reducing the core size and/or the NA, as seen in the following relationship, where a is the fiber radius, and λ is the operating wavelength, n_{co} and n_{cl} are the refractive indices of the core and the cladding, respectively.

Raman Scattering in Sapphire Fibers





Objective

- Develop a micro-structured sapphire fiber sensor with low modal volume (LMV).
- Demonstrate a Raman scattering based distributed temperature sensing system.

Scope

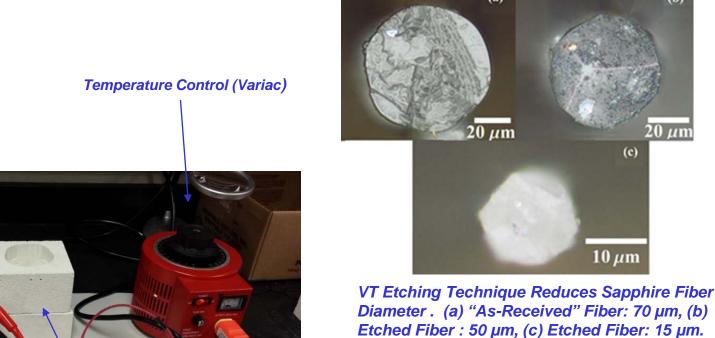
- Evaluate the improvement introduced by the Low Mode Volume sapphire fiber in a wafer-based sensor system.
- Develop a prototype sensing system with fully-distributed sensing capacity and evaluate its performance in

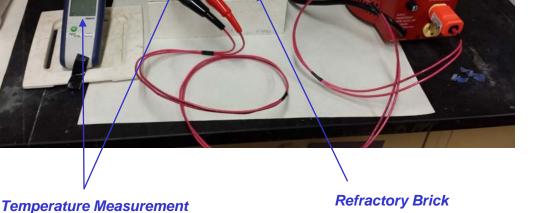
Etching Solution Vessel

 $V = \frac{2\pi}{\lambda} a NA = \frac{2\pi}{\lambda} a \sqrt{n_{co}^2 - n_{cl}^2}$

• A reduction in fiber diameter and/or numerical aperture will reduce the V number, and in turn, significantly reduce the number of modes propagating in the fiber.

Single Crystal Sapphire Etching









Sapphire wafer masked with Teflon[™] during etching process.

• The microstructure and size of single crystal sapphire fibers are tailored via a wet acid etching technique. Fibers are exposed to sulfuric (H_2SO_4) and phosphoric (H_3PO_4) at elevated temperatures (300°C - 500°C)

> $Al_2O_3 + 6H_3PO_4 \leftrightarrow 2Al(H_2PO_4)_3 + 3H_2O$ (1)

a laboratory test environment for operation at temperatures over 1100°C.

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Researchers

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Sponsors

National Energy Technology Laboratory of the U.S. Department of Energy (DOE)

	$Al(H_2PO_4)_3 + Al_2O_3 \leftrightarrow 3AlPO_4 + 3H_2O $ (2) $Al^{+3} + nSO_4^{-2} \leftrightarrow Al_2(SO_4)_n^{-3-2n} $ (3) $2Al^{+3} + 3SO_4^{-2} \leftrightarrow Al_2(SO_4)_3 + xH_2O $ (4)
3	Sapphire "Microstructuring"
	Angled Edge on Single Crystal Sapphire Wafer via VT Etching Process
	10 μm
	Image of etched sapphire fiber via polarized light; the birefringence is due to the attenuated hexagonal structure of the material.Potential Alumina Porous/Solid Cladding via Virginia Tech "Conversion" Technology.
	 Masking techniques are currently being explored to form features in the sapphire fiber via Teflon [™] and silica masking techniques.
	 Reflective edge features and attenuated hexagon shaped fibers have been demonstrated via selected processing parameters.
	 Novel silicon carbide masking and "conversion" techniques are currently being investigated as potential cladding processes.





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